ATTY DKT. No.: AMAT/8629/FEP/GCM/RKK U.S. SERIAL No.: Unknown FILED: Herewith APPLIED MATERIALS, INC.

A Method of Forming a Silicon Oxynitride

Christopher Olsen, et al.

Layer

INVENTOR: EXPRESS MAIL NO.: EV335470144US

PAGE 1 OF 6

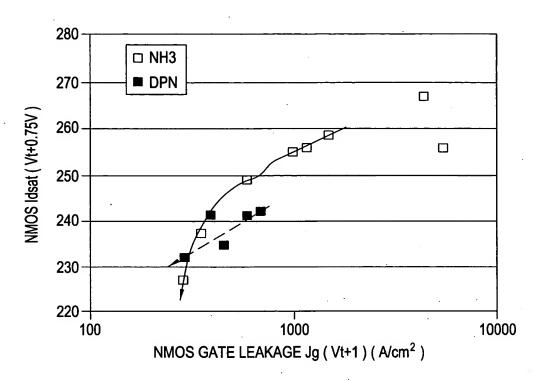


FIG. 1

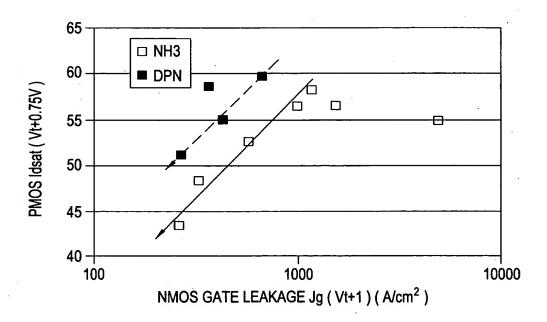


FIG. 2

ATTY DKT. No.: AMAT/8629/FEP/GCM/RKK
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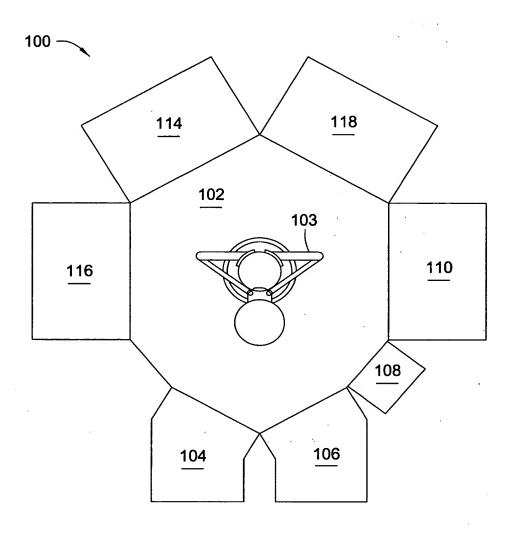


FIG. 3

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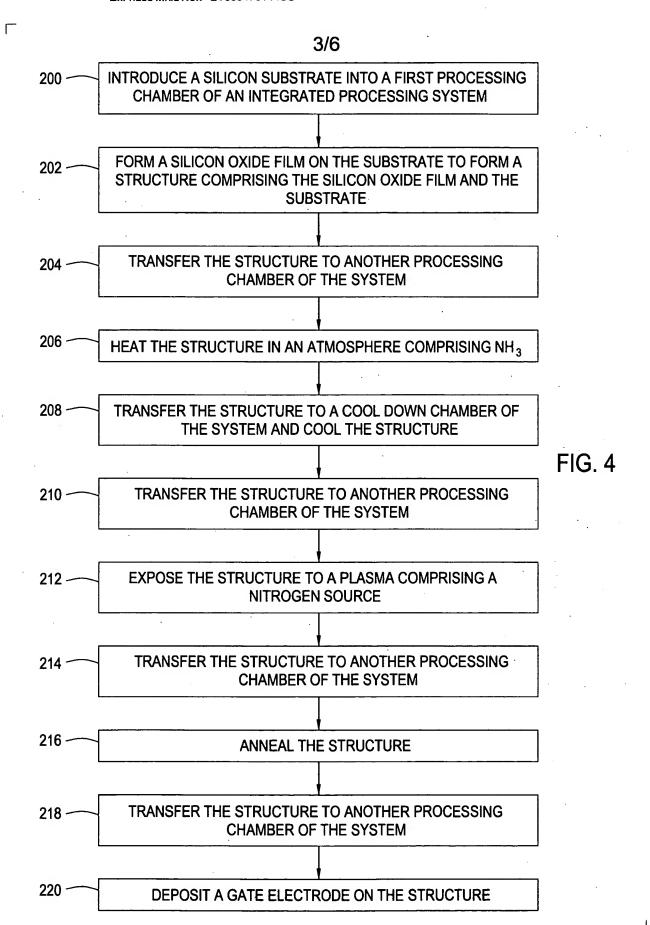
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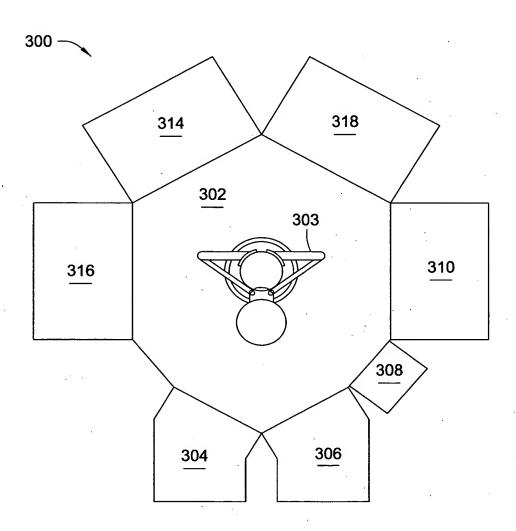


FIG. 5

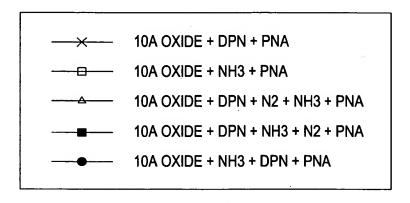
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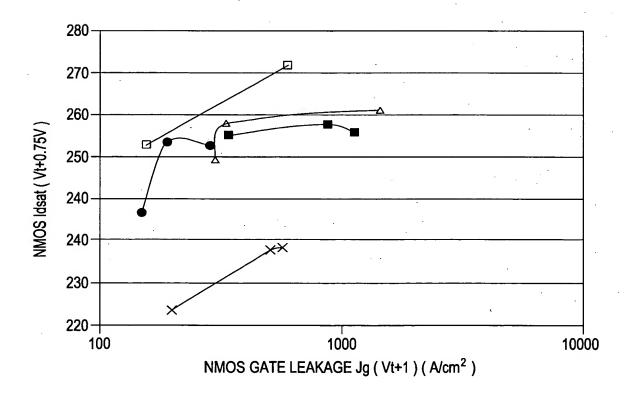


FIG. 6

ATTY DKT. NO.: AMAT/8629/FEP/GCM/RKK U.S. SERIAL NO.: Unknown FILED: Herewith APPLICANT: APPLIED MATERIALS, INC.

TITLE: A N

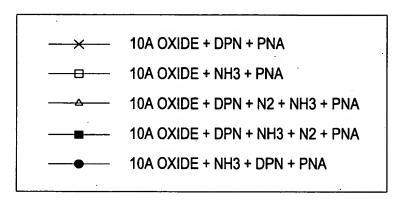
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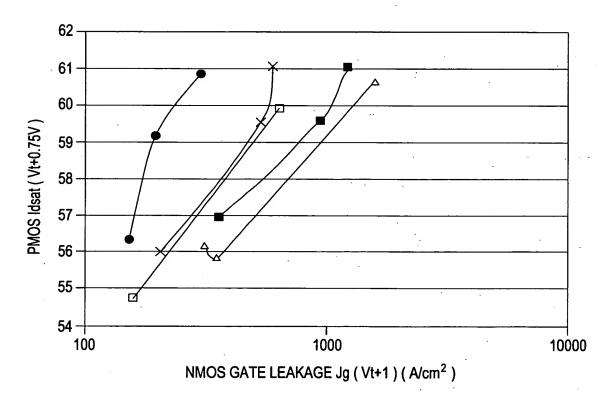


FIG. 7